

POSITIVE RESIST COMPOSITION FOR ELECTRON BEAM OR X RAY

Publication number: JP2002341538

Publication date: 2002-11-27

Inventor: SASAKI TOMOYA; MIZUTANI KAZUYOSHI;
SHIRAKAWA KOJI

Applicant: FUJI PHOTO FILM CO LTD

Classification:

- international: G03F7/039; G03F7/004; H01L21/027; G03F7/039;
G03F7/004; H01L21/02; (IPC1-7): G03F7/039;
G03F7/004; H01L21/027

- European:

Application number: JP20010142185 20010511

Priority number(s): JP20010142185 20010511

Report a data error here

Abstract of JP2002341538

PROBLEM TO BE SOLVED: To provide a positive resist composition for electron beams or X rays having high sensitivity, high resolution and excellent stability of PED(post exposure delay). **SOLUTION:** The positive resist composition for electron beams or X rays contains (a) a compound which produces an acid by irradiation with electron beams or X rays, (b) a resin which increases the solubility to an alkali developer by the effect of an acid, (c) a low molecular weight compound stable against acid and having a residue of a compound showing the ionization potential (Ip) lower than the Ip of p-ethylphenol, and (d) a solvent.

Data supplied from the **esp@cenet** database - Worldwide